

**A SYSTEM AND METHOD FOR PREDICTING A PARAMETER
FOR A LITHOGRAPHY OVERLAY FIRST LOT**

ABSTRACT

[0033] A system and method are provided for establishing a process parameter for manufacturing a semiconductor product prior to receiving manufacturing feedback regarding the process parameter. In one example, the method includes identifying a technology to which the process parameter is related and identifying at least one existing part manufactured using the identified technology. Information reflecting feedback data obtained while manufacturing the part may be retrieved and the process parameter may be calculated based on the retrieved information.